



Molecular Imprints, Inc.

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**MOLECULAR IMPRINTS LAUNCHES ITS NEWEST AND MOST ADVANCED PRODUCT  
– THE IMPRIO 250**

AUSTIN, TX, February 28, 2005 – Molecular Imprints, Inc. (MII), the world leader in Step and Flash Imprint Lithography (S-FIL™) technology, announces the launch of the industry's most advanced imprint lithography system – the Imprio™ 250. Molecular Imprints' newest nano-imprint system represents the next generation in lithography. The Imprio 250 offers sub-50 nm half-pitch resolution, sub-10 nm alignment, as well as integrated magnification control, and delivers high resolution and precision alignment for customers seeking cost-effective sub-50 nm lithography.

This advanced tool is built to semiconductor industry standards around a core platform using Step and Flash Imprint Lithography (S-FIL) technology. The Imprio 250 includes fully automated wafer handling (up to 300 mm) and automated template loading capability. The tool has a novel, in-liquid alignment and magnification control system for precision overlay for advanced lithography applications.

Norm Schumaker, MII's President and CEO said: "We are very happy to be able to announce the availability of the Imprio 250. It was designed and engineered in close cooperation with our expanding customer base who need the advantages of S-FIL technology in the production of their devices and components. The Imprio 250 is an important step in our plans to make S-FIL the technology of choice for patterning features below 100nm."

For more information on the Imprio 250, contact Molecular Imprints at [info@molecularimprints.com](mailto:info@molecularimprints.com).

**About Molecular Imprints Inc.**

Molecular Imprints, Inc. (MII) is a global developer and manufacturer of nano-lithography systems for high resolution and for 3-dimensional pattern replication. The company has commercialized the unique Step and Flash Imprint Lithography technology (S-FIL), which is a simple step and repeat, room temperature, low pressure, nano-imprint process that has demonstrated sub-20 nanometer resolution. Molecular Imprints provides enabling lithography systems and technology for manufacturing applications in the areas of: nano-devices, micro structures, advanced packaging, bio-devices, optical components and semiconducting devices. For more information, visit: [www.molecularimprints.com](http://www.molecularimprints.com).

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